

Fig. 2 Upper lined of 730 4 patent (Continuous annealing) 1.0 H20/H2 Upper limit of 750 patent (galvanising) 5 Upper limit of the present invention 0.5 Lower lint of 750 Patent (Continuous arnealing) 3 0.0 Lower limit of the present invention 650 700 750 800 850 900 Temperature(°C

Difference of H20/pH2 ratio between the present invention and > 730 patent

H2O/PH2の本願と引例1の差異